

Radiation tolerant materials for semiconductor tracking detectors at SuperLHC

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- ✓ **Motivation to develop radiation harder detectors**
- ✓ **Introduction to the RD50 collaboration**
- ✓ **Radiation Damage**
- ✓ **Material Engineering**
- ✓ **Summary**

Large Scale Application of Si Detectors in High Energy Physics Experiments

LHC: Present working conditions:

$L \sim 10^{34} \text{ cm}^{-2}\text{s}^{-1}$ within 10 years fast hadron fluence:

$f \sim 10^{15} \text{ n/cm}^2$ for pixels



$f \sim 10^{14} \text{ n/cm}^2$ for microstrips

LHC upgrade (“Super-LHC” ... later than 2010)

$L \sim 10^{35} \text{ cm}^{-2}\text{s}^{-1}$ \Rightarrow fluence up to 10^{16} cm^{-2} *after five years*

R&D needed for the development of a detector technology able to operate safely and efficiently in such an environment.

Anticipated Radiation Environment for Super LHC

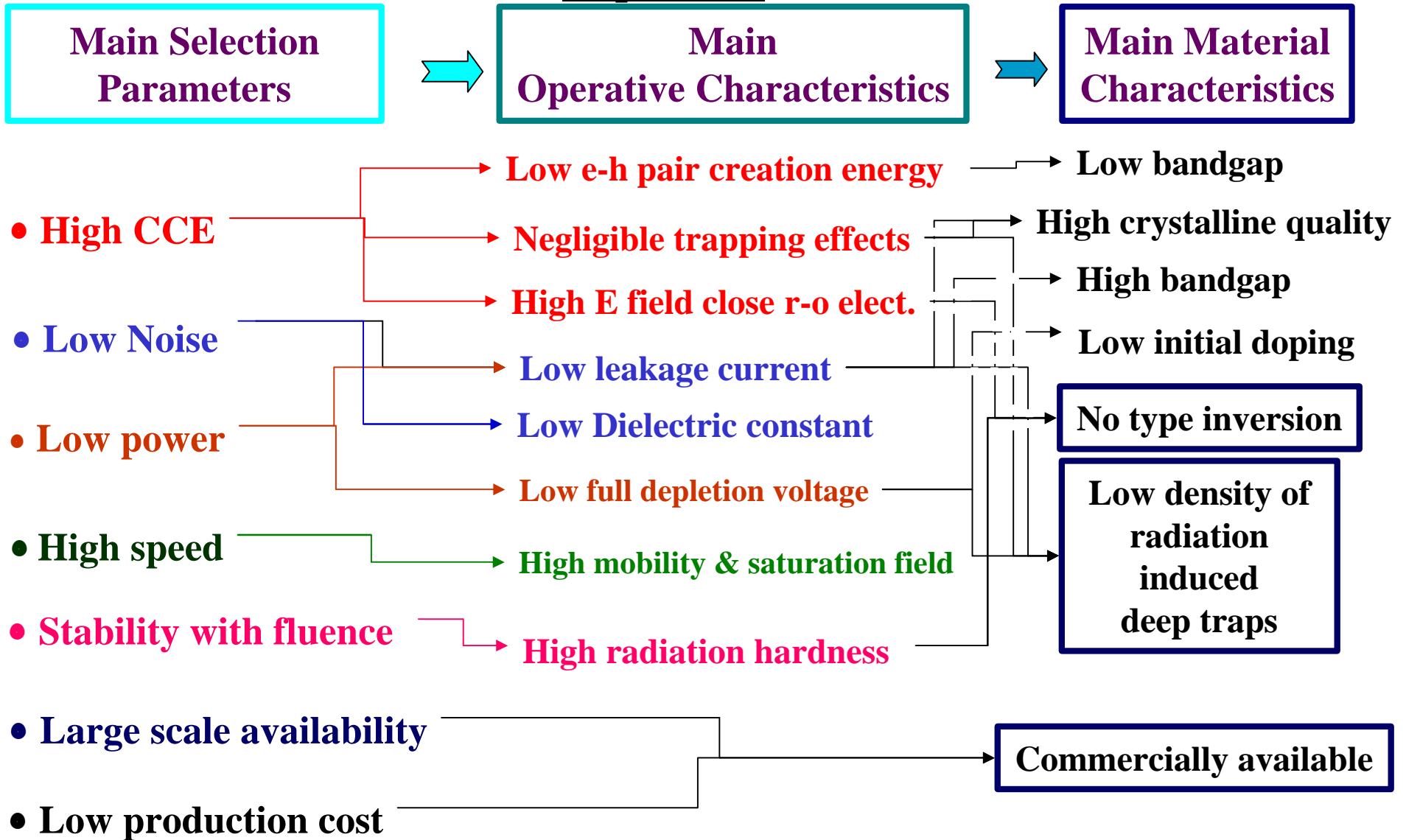
Hadron fluence and radiation dose in different radial layers of the CMS tracker for an integrated luminosity of 2500fb^{-1} . (CERN-TH/2002-078)

Radius (cm)	Fluence of fast hadrons [cm^{-2}]	Dose [KGy]
4	1.6×10^{16}	4200
11	2.3×10^{15}	940
22	8.0×10^{14}	350
75	1.5×10^{14}	35
115	1.0×10^{14}	9.3

Proposal to split the tracker volume into 3 radial regions:

- 1. $R > 60\text{cm}$ improved Si strip technology**
- 2. $20\text{cm} < R < 60\text{cm}$ improved hybrid pixel technology**
- 3. $R < 20\text{cm}$ new approaches and concepts required**

Selecting Radiation- Hard materials for tracker detectors at SuperLHC



Status of radiation-hard materials for tracking detectors

at SLHC

Property	Si	Diamond	Diamond	4H SiC
Material Quality	Cz, FZ, epi	Polycrystalline	single crystal	epitaxial
E_g [eV]	1.12	5.5	5.5	3.3
$E_{\text{breakdown}}$ [V/cm]	$3 \cdot 10^5$	10^7	10^7	$2.2 \cdot 10^6$
m_e [cm^2/Vs]	1450	1800	>1800	800
m_h [cm^2/Vs]	450	1200	>1200	115
v_{sat} [cm/s]	$0.8 \cdot 10^7$	$2.2 \cdot 10^7$	$2.2 \cdot 10^7$	$2 \cdot 10^7$
Z	14	6	6	14/6
ϵ_r	11.9	5.7	5.7	9.7
e-h energy [eV]	3.6	13	13	7.6
Density [g/cm ³]	2.33	3.515	3.515	3.22
Displacem. [eV]	13-20	43	43	25
e-h/mm for mip	89	36	36	55
Max initial ccd [mm]	>500	280	550	40 (= thickness)
Max wafer f tested	6''	6''	6mm	2''
Producer	Several	Element-Six	Element-Six	Cree-Alenia, IKZ
Max fluence [cm^{-2}]	7×10^{15} 24GeV p	2×10^{15} n, p, p	Not reported	10^{16} in progress
CERN R&Ds	RD50, RD39	RD42	RD42	RD50



See H. Kagan Talk



See Kinoshita Talk

❑ **RD-2 SITP (1990-1994)**

Study of a Tracking/Preshower Detector for the LHC

❑ **RD-8 GAASWORKS (1991-1995)**

Development of GaAs Detectors for Physics at the LHC

❑ **RD-19 PIXEL (1991-2000)**

Development of Hybrid and Monolithic Silicon Micropattern Detectors

❑ **RD-20 Si TRACKER(1990-1994)**

Development of High Resolution Si Strip Detectors for Experiments at High Luminosity LHC

❑ **RD39 SMSD (1994 – present)**

Cryogenic Tracking Detectors ® **J. Harkonen talk, this session**

❑ **RD42 (1994 – present)**

® **H. Kagan talk, this session**

Development of Diamond Tracking Detectors for High Luminosity Experiments at the LHC

❑ **RD48 ROSE (1996-2000)**

Radiation Hardening of Silicon Detector

❑ **RD49 RADTOL (1997-2000)**

Studying Radiation Tolerant ICs for LHC

❑ **RD50 (2002 -)**

Development of Radiation Hard Semiconductor Devices for Very High Luminosity Colliders

The RD50 CERN Collaboration

Development of Radiation Hard Semiconductor Devices for High Luminosity Colliders

- Collaboration formed in November 2001 - <http://www.cern.ch/rd50>
- Experiment approved as RD50 by CERN in June 2002
- Main objective:

Development of ultra-radiation hard semiconductor detectors for the luminosity upgrade of the LHC to $10^{35} \text{ cm}^{-2}\text{s}^{-1}$ (“Super-LHC”).

Challenges:

- Radiation hardness up to 10^{16} cm^{-2} required
- Fast signal collection (10 ns bunch crossing)
- Low mass (reducing multiple scattering close to interaction point)

- Cost effectiveness

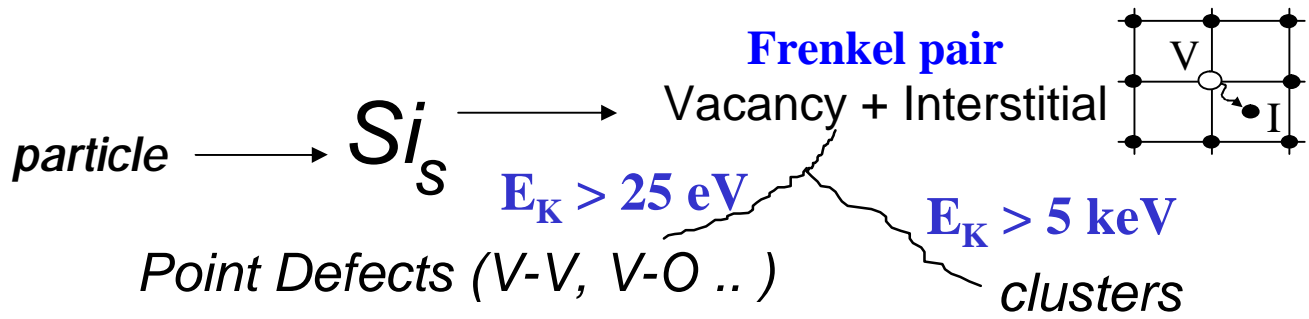
- Presently 280 Members from 55 Institutes

Belgium (Louvain), **Canada** (Montreal), **Czech Republic** (Prague (2x)), **Finland** (Helsinki (2x), Oulu), **Germany** (Berlin, Dortmund, Erfurt, Halle, Hamburg, Karlsruhe), **Greece** (Athens), **Israel** (Tel Aviv), **Italy** (Bari, Bologna, Florence, Milano, Modena, Padova, Perugia, Pisa, Trento, Trieste, Turin), **Lithuania** (Vilnius), **Norway** (Oslo (2x)), **Poland** (Warsaw), **Romania** (Bucharest (2x)), **Russia** (Moscow (2x), St.Petersburg), **Slovenia** (Ljubljana), **Spain** (Barcelona, Valencia), **Sweden** (Lund) **Switzerland** (CERN, PSI), **Ukraine** (Kiev), **United Kingdom** (Exeter, Glasgow, Lancaster, Liverpool, London, Sheffield, University of Surrey), **USA** (Fermilab, Purdue University, Rutgers University, Syracuse University, BNL, University of New Mexico)

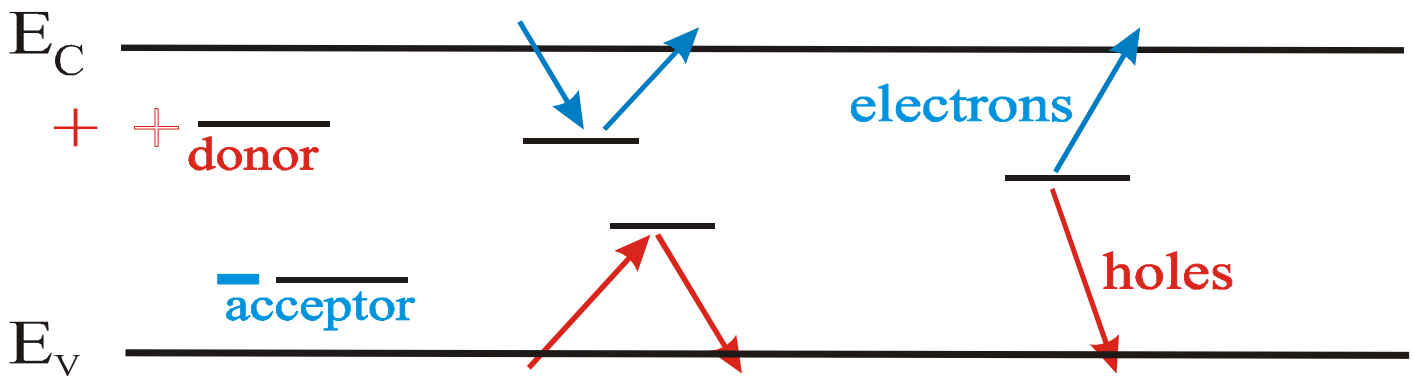
Scientific strategies

- **Material Engineering**
 - **Defect and Material Characterisation**
 - **Defect engineering of silicon**
 - **New detector materials (SiC, ..)**
- **Device Engineering**
 - **Improvement of present planar detector structures (3D detectors, thin detectors, cost effective detectors,...)**
 - **Tests of LHC-like detector systems produced with radiation-hard technology**

Radiation Induced Microscopic Damage in Silicon



Influence of defects on the material and device properties



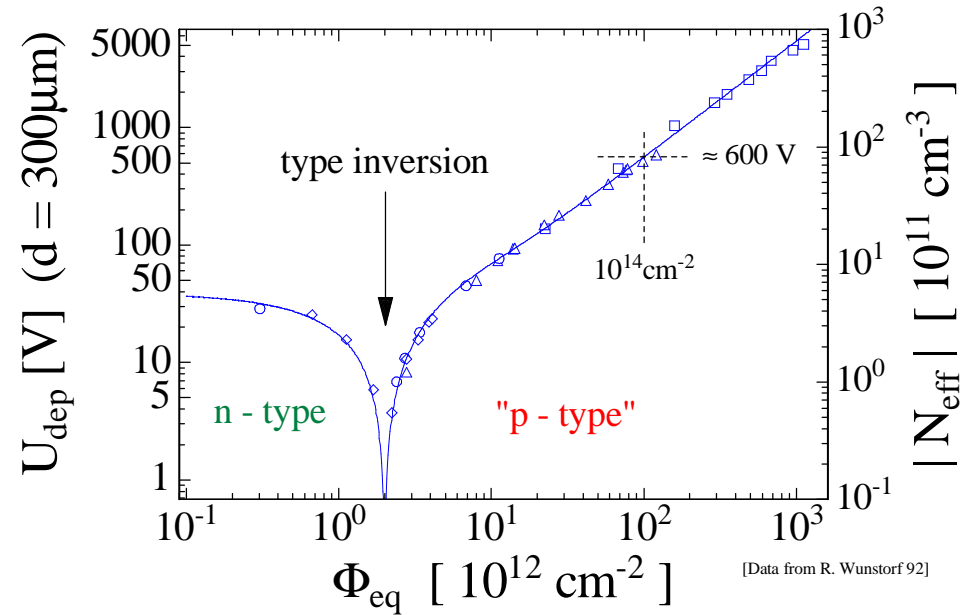
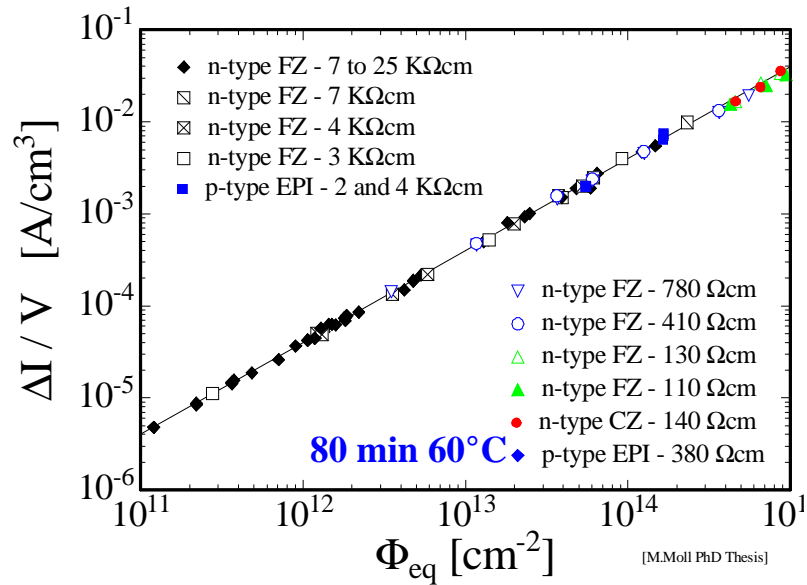
charged defects
 $\mathbb{P} N_{\text{eff}}, V_{\text{dep}}$
 e.g. donors in upper
 and acceptors in
 lower half of band
 gap

Trapping (e and h)
 $\mathbb{P} \text{CCE}$
 shallow defects do not
 contribute at room
 temperature due to fast
 detrapping

generation
 $\mathbb{P} \text{leakage current}$
 Levels close to
 midgap
 most effective

Leakage Current

V_{dep}, N_{eff}

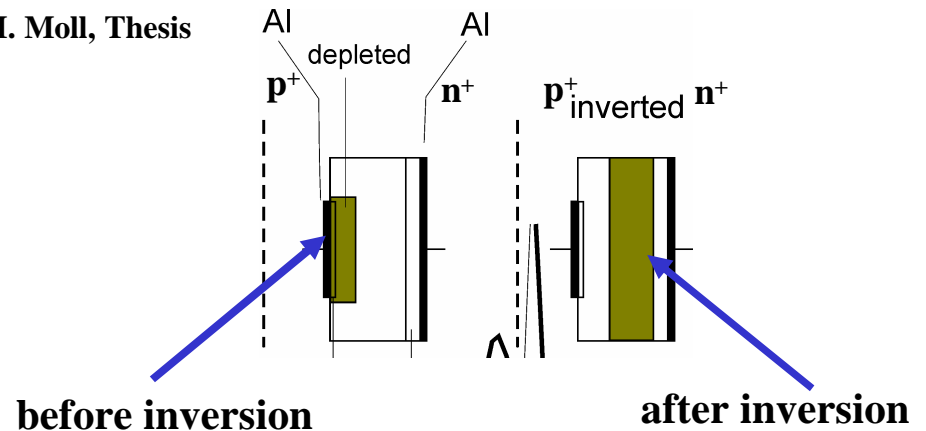


- **Damage parameter a (slope)**

$$a = \frac{\Delta I}{V \cdot \Phi_{eq}}$$

- **a independent of F_{eq} and material kind**

M. Moll, Thesis



Charge Collection Efficiency

- Limited by:
- **Partial depletion**
 - **Trapping at deep levels**
 - **Type inversion**

Collected Charge: $Q = Q_o \cdot e_{dep} \cdot e_{trap}$

$$e_{dep} = \frac{d}{W} \quad e_{trap} = e^{-\frac{t_c}{t_t}}$$

W: total thickness
 d: Active thickness
 τ_c : Collection time
 τ_t : Trapping time

Trapping time reduced by radiation:

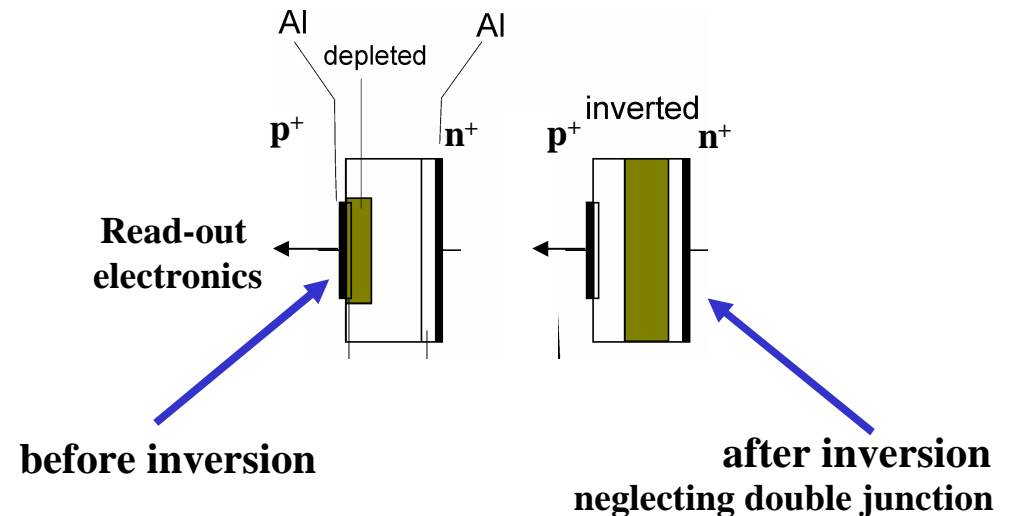
Krasel et al. (RD50)

for e/h up to 10^{15} cm^{-2} n- Si:

$$1/\tau_t = 5 \cdot (F/10^{16}) \text{ ns}^{-1}$$

$$\tau_t \sim 1/F$$

$$\tau_t = 0.2 \text{ ns for } F = 10^{16} \text{ cm}^{-2}$$



Defect Engineering of Silicon

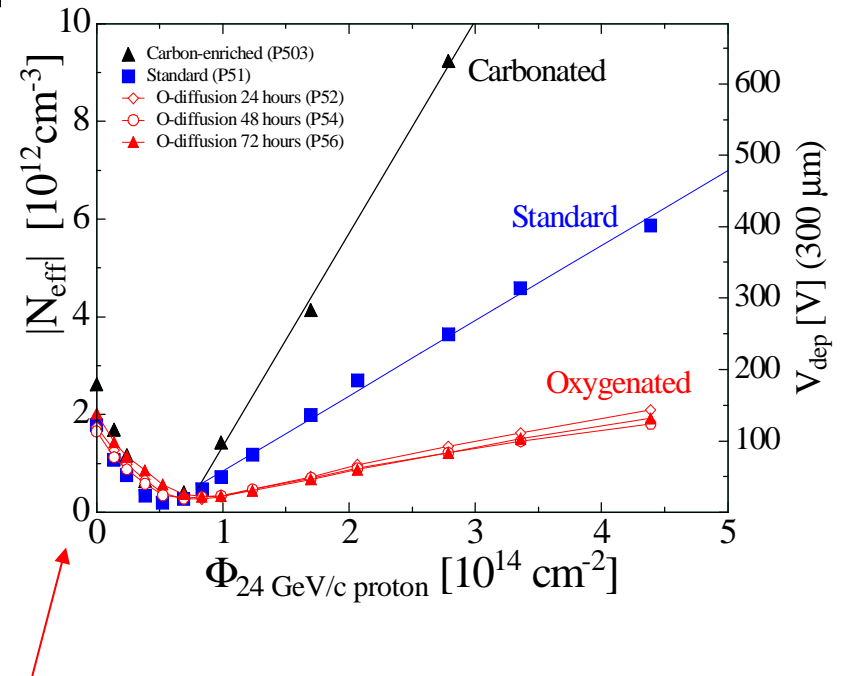
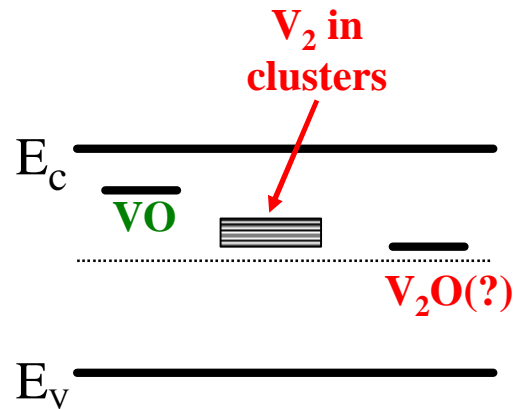
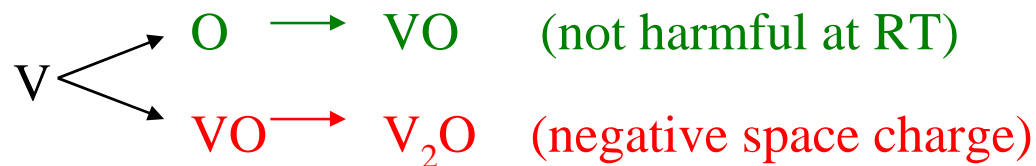
Influence the defect kinetics by incorporation of impurities or defects: Oxygen

Initial idea: **Incorporate Oxygen to getter radiation-induced vacancies**

⇒ **prevent formation of Di-vacancy (V_2) related deep acceptor levels**

• Higher oxygen content ⇒ less negative space charge

One possible mechanism: V_2O is a deep acceptor



DOFZ (Diffusion Oxygenated Float Zone Silicon) RD48 NIM A (1999)

Different kind of Si materials investigated by RD50

Material	Symbol	r W cm	[O _i] cm ⁻³
Standard n- or p-type FZ	STNFZ	1-7 · 10 ³	< 5 · 10 ¹⁶
Diffusion Oxygenated FZ p- or n-type	DOFZ	1-7 · 10 ³	~ 1-2 · 10 ¹⁷
Epi-layer 50 μm on CZ n-type ITME	EPI	50-100	substrate: 1 · 10 ¹⁸
Czochralski Sumitomo, Japan	CZ	1.2 · 10 ³	~ 8-9 · 10 ¹⁷
Magnetic Czochralski Okmetic Finland	MCZ	1.2 · 10 ³	~ 5-9 · 10 ¹⁷

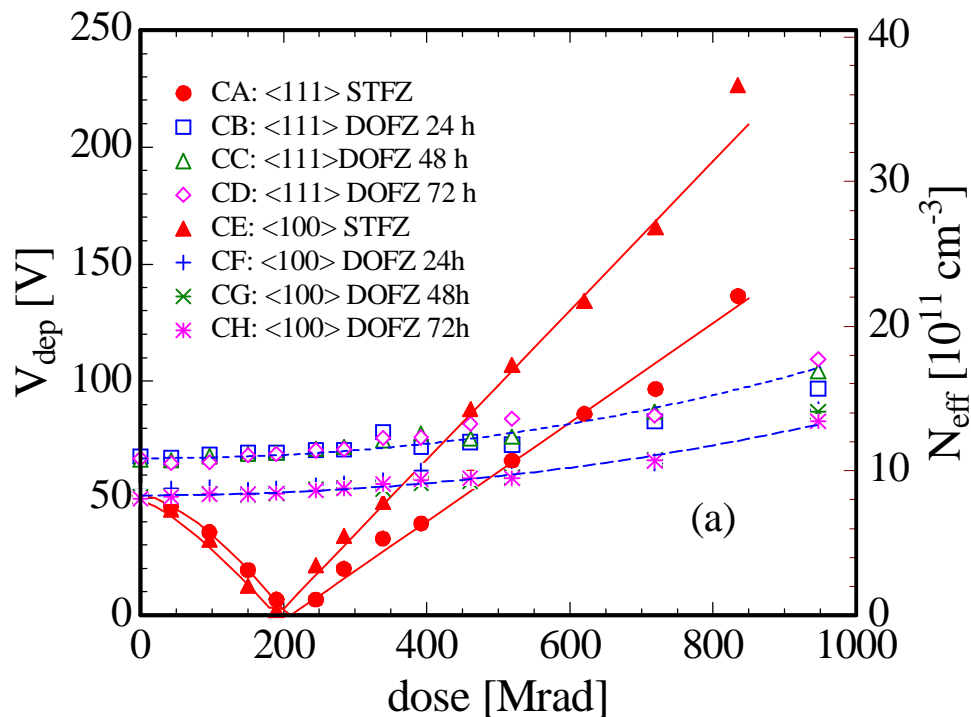
Czochralski Si

See also talk of J. Harkonen

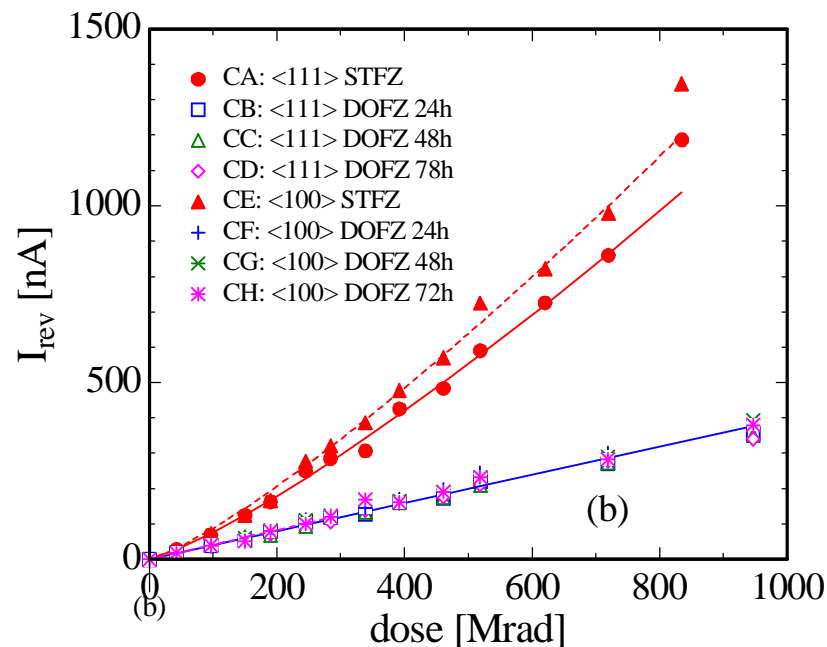
- Very high Oxygen content 10¹⁷-10¹⁸cm⁻³ (**Grown in SiO₂ crucible**)
- High resistivity (>1kΩcm) available only recently (**Magnetic CZ technology**)
- CZ wafers cheaper than FZ (**RF-IC industry got interested**)

DOFZ Si: Spectacular Improvement of γ -irradiation tolerance

Depletion Voltage



Leakage Current



- No type inversion for oxygen enriched silicon!
- Slight increase of positive space charge
(due to **Thermal Donor generation?**)
- Leakage increase not linear and depending on oxygen concentration

[E.Fretwurst et al. 1st RD50 Workshop]

See also:

- Z.Li et al. [NIMA461(2001)126]

- Z.Li et al. [1st RD50 Workshop]

Characterization of microscopic defects

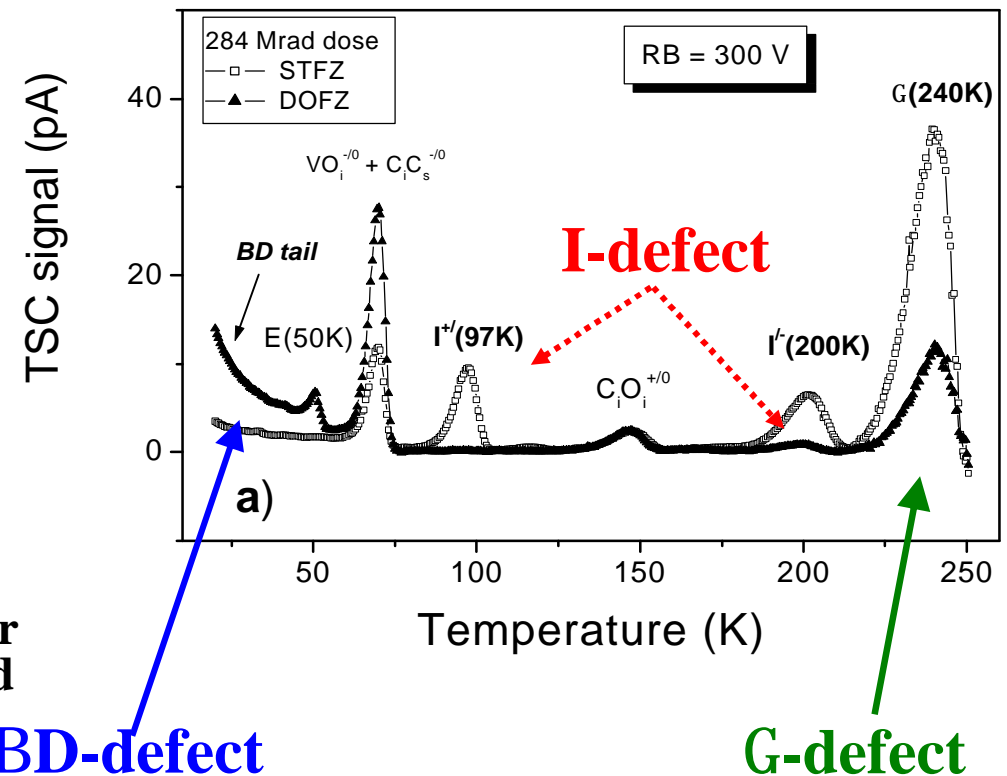
- γ -irradiated silicon detectors -

- **For the first time** macroscopic changes of the depletion voltage and leakage current can be explained by electrical properties of measured defects \rightarrow **Major breakthrough!**

I.Pintilie et al., Applied Physics Letters, 82, 2169, March 2003

Levels responsible for macroscopic changes after γ -irradiation:

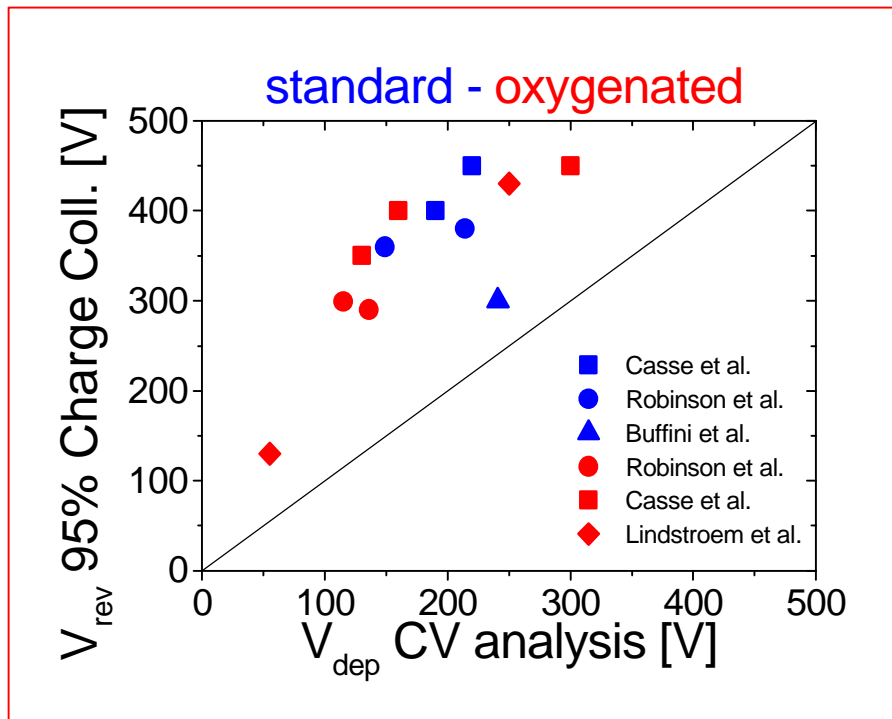
- I-defect: acceptor level at $E_C - 0.54\text{eV}$ (coming up for approx. 85% of damage)
peculiarity: quadratic dose dependence
 \Rightarrow **is this the V_2O defect?**
- Γ -defect: acceptor level at $E_V + 0.68\text{eV}$ (coming up for approx. 10% of damage)
- BD-defect: bistable shallow thermal donor (important in oxygen enriched silicon)



Discrepancy between CCE and CV analysis with p⁺n devices

In segmented p⁺n detectors read-out with LHC-like electronics above the CV-derived depletion voltage, the CCE continues to rise significantly with bias. **To maximise CCE overdepletion**

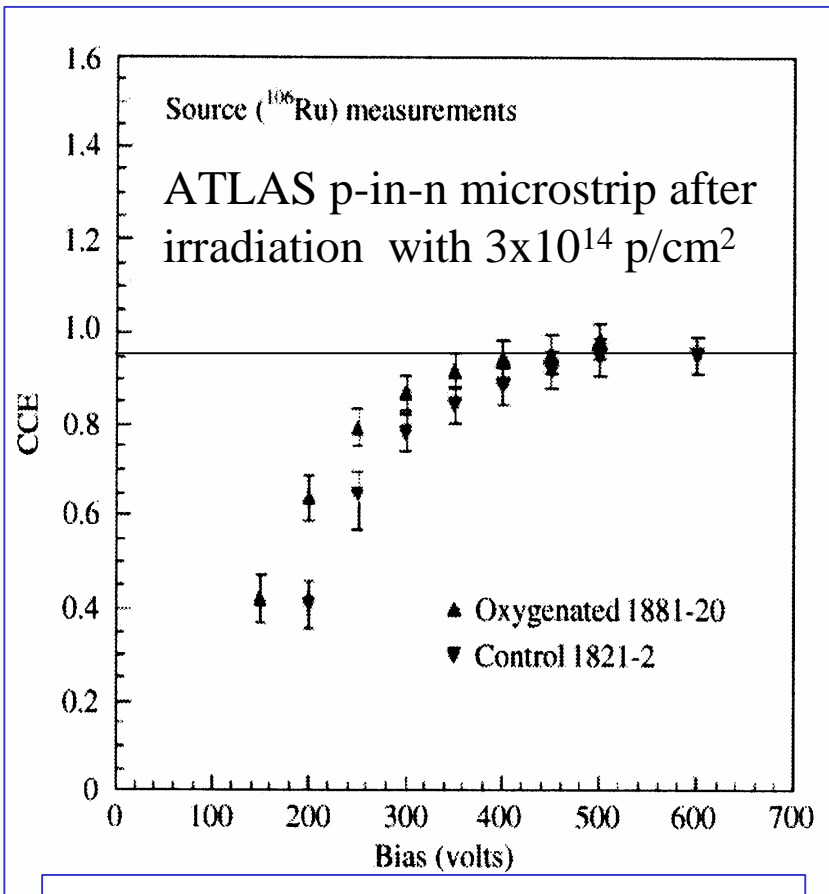
$V_{CCE} \sim 2V_{dep}$ is needed both in n-type standard and oxygenated Si.



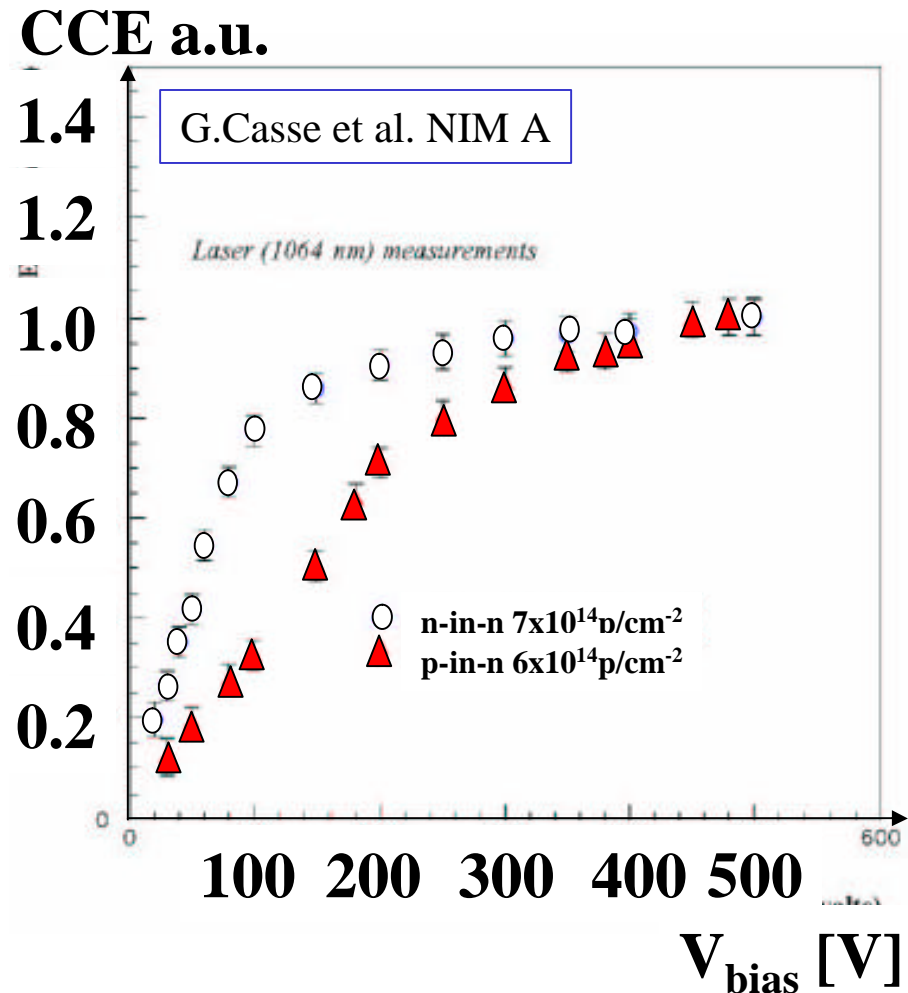
	Author	radiation	Exp.	material
?	Robinson et al., NIM A 461 (2001)	3×10^{14} 24GeV p/cm ²	ATLAS	Oxygen. + standard
!	Casse et al., NIM A 466 (2001)	$3-4 \times 10^{14}$ 24GeV p/cm ²	ATLAS	Oxygen. + standard
?	Lindström et al., NIM A 466 (2001)	1.65×10^{14} 24GeV p/cm ²	ROSE	Oxygen. <100>
?	Buffini et al., NIM A (2001) in press	1.1×10^{14} 1MeV n/cm ²	CMS	Standard <111>

Same behavior for standard and oxygenated (DOFZ), <100> and <111>Si

The beneficial effect of oxygen in proton irradiated DOFZ p⁺n Si microstrips almost disappear in CCE measurements due to type inversion. Better results achieved with n-in-n detectors.



G.Casse et al. NIM A 466 (2001) 335-344



Recent results with n-in-p microstrip detectors

Liverpool & CNM-Barcelona within RD50

Data presented by G. Casse at Vienna Conference, February 2004

□ Miniature n-in-p microstrip detectors (280mm thick) produced by CNM-Barcelona using a mask-set designed by the University of Liverpool.

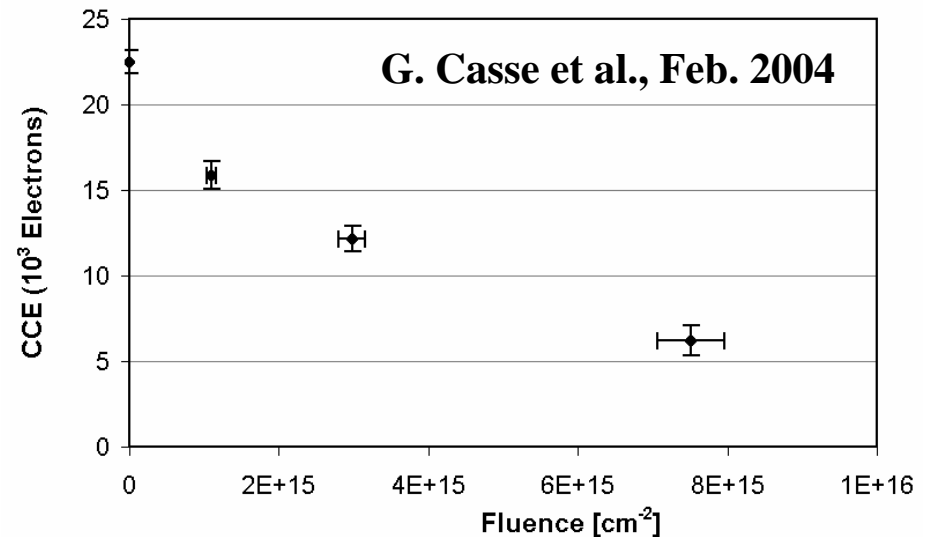
□ Detectors read-out with a SCT128A LHC speed (40MHz) chip

□ Material: standard p-type and oxygenated (DOFZ) p-type

□ Irradiation: 24GeV protons up to $3 \cdot 10^{15} \text{ p cm}^{-2}$ (standard) and $7.5 \cdot 10^{15} \text{ p cm}^{-2}$ (oxygenated)

CCE ~ 60% after $3 \cdot 10^{15} \text{ p cm}^{-2}$ at 900V (standard p-type)

CCE ~ 30% after $7.5 \cdot 10^{15} \text{ p cm}^{-2}$ 900V (oxygenated p-type)

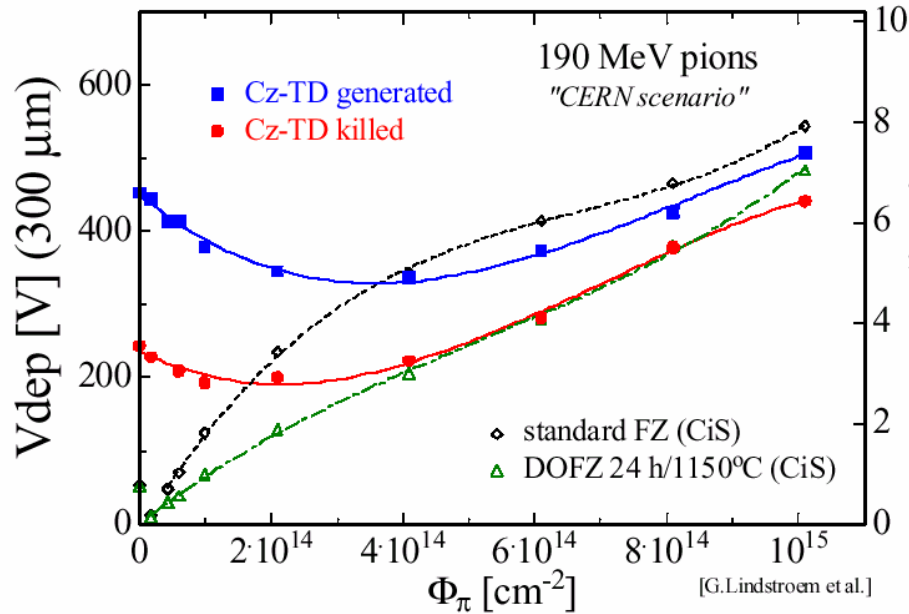


At the highest fluence $Q \sim 6500e$ at $V_{\text{bias}} = 900V$ corresponding to: $\text{ccd} \sim 90\mu\text{m}$

n-type Czochralski Si

190 MeV p irradiation Villigen

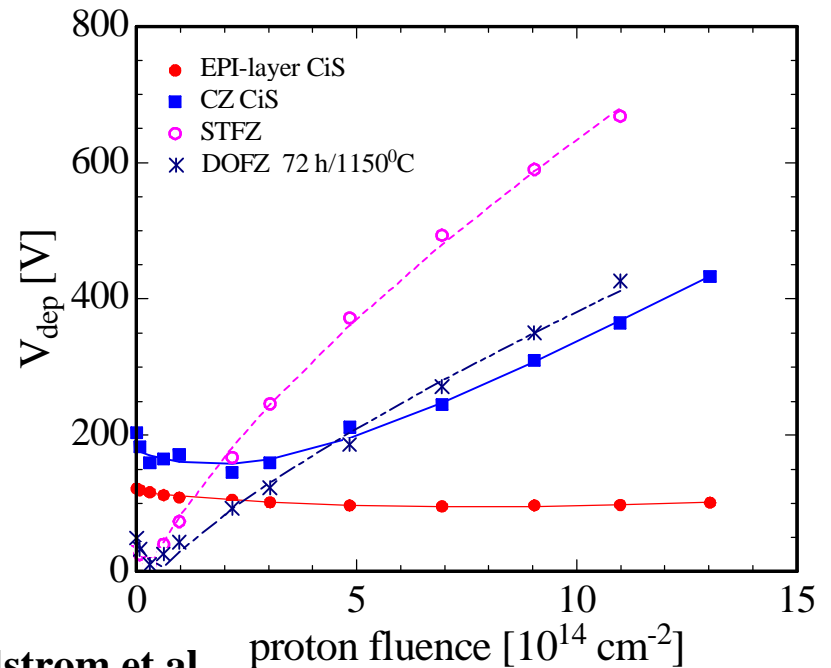
Cz from Sumitomo Sitix, Japan



Data From G.Lindstrom et al.

24 GeV/c p irradiation CERN

Cz from Sumitomo Sitix, Japan



◆ No type inversion (SCSI)

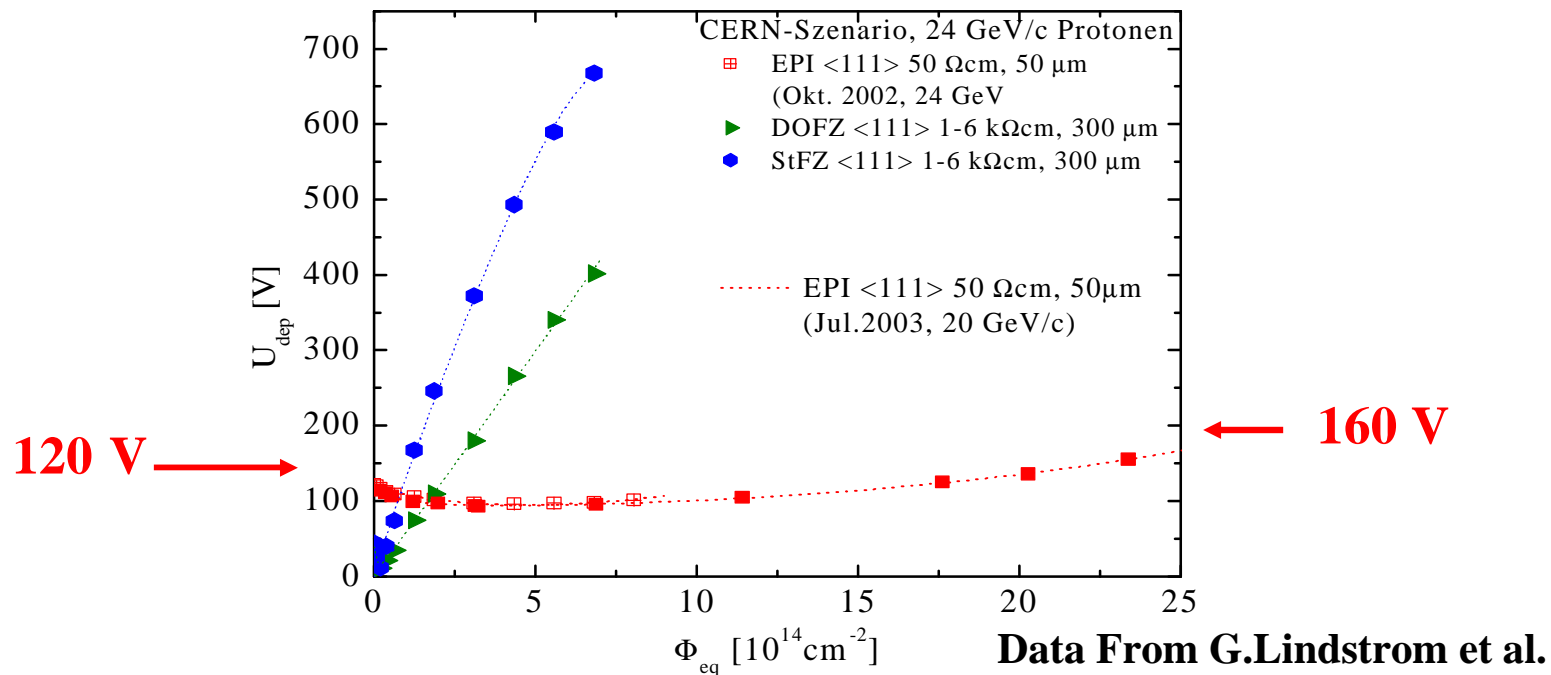
◆ Reverse current and charge trapping comparable to FZ silicon

◆ Charge collection efficiency under study

Epitaxial silicon

Motivation: After 1 MeV neutron irradiation to 10^{15} cm^{-2}
the effective drift length for e is $\sim 150 \mu\text{m}$ and for h $\sim 50 \mu\text{m}$

P use thin detectors (50-100 μm) from the beginning, with low resistivity Epitaxial Si
50 μm , 50 Ωcm on CZ Si made by ITME (Warsaw)

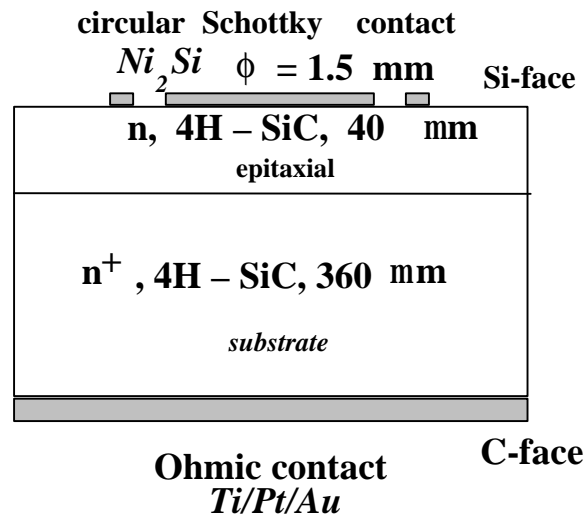


- Leakage current almost identical to CZ, FZ, DOFZ detectors
- CCE with β -source under study

New Materials: Epitaxial SiC

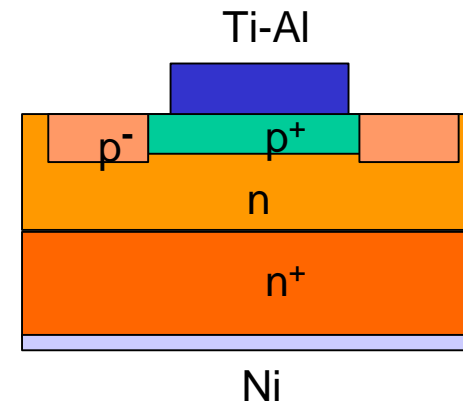
- **Semi-Insulating SiC**
 - $\rho > 10^{11} \Omega\text{cm}$ due to vanadium compensation
 - CCE 60% in as-grown, $\sim 55\%$ after irradiation with 10^{13}cm^{-2} 300 MeV/c π
 - Vanadium is responsible of incomplete charge collection
- **Epitaxial 4H-SiC**
 - 6 new 2'' wafers $d \sim 50\mu\text{m}$, $N_{\text{eff}} = 5 \cdot 10^{13}\text{cm}^{-3}$ produced by CREE and IKZ, Berlin
 - Common RD50 test structures produced and irradiated

Schottky Barrier detector



Modena&Alenia Systems, Italy

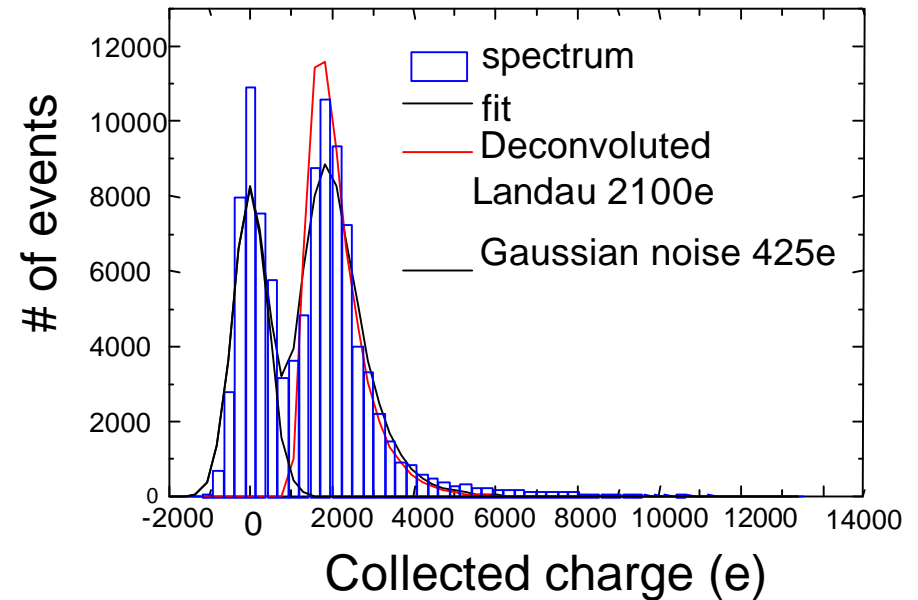
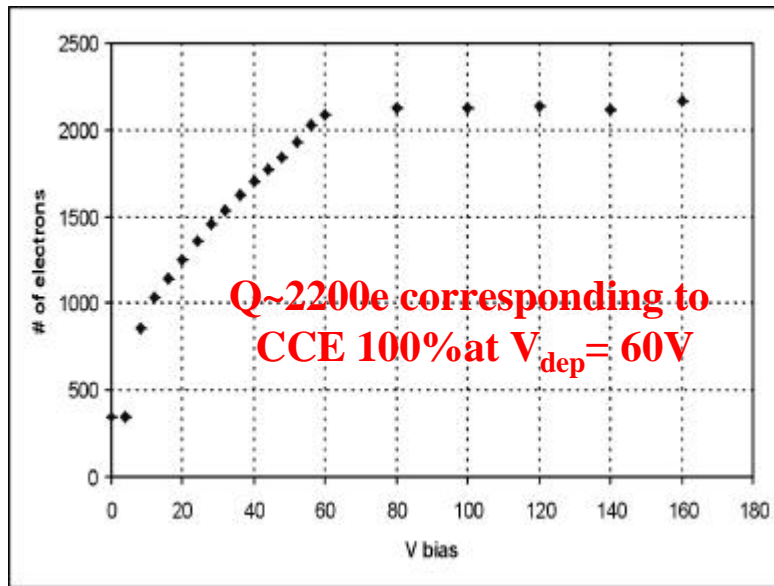
p^+n junction detector



Perugia&IMM Bologna,Italy

Epitaxial SiC Schottky Barriers

- ◆ n epilayer $N_{\text{eff}} \sim 5 \cdot 10^{13} \text{cm}^{-3}$ 40mm by IKZ Berlin on CREE substrate; Schottky contacts
- ◆ No priming / polarization effects observed
- ◆ Charge collection efficiency tested with α ^{241}Am and β ^{90}Sr
100% before irradiation: 2200e with mips



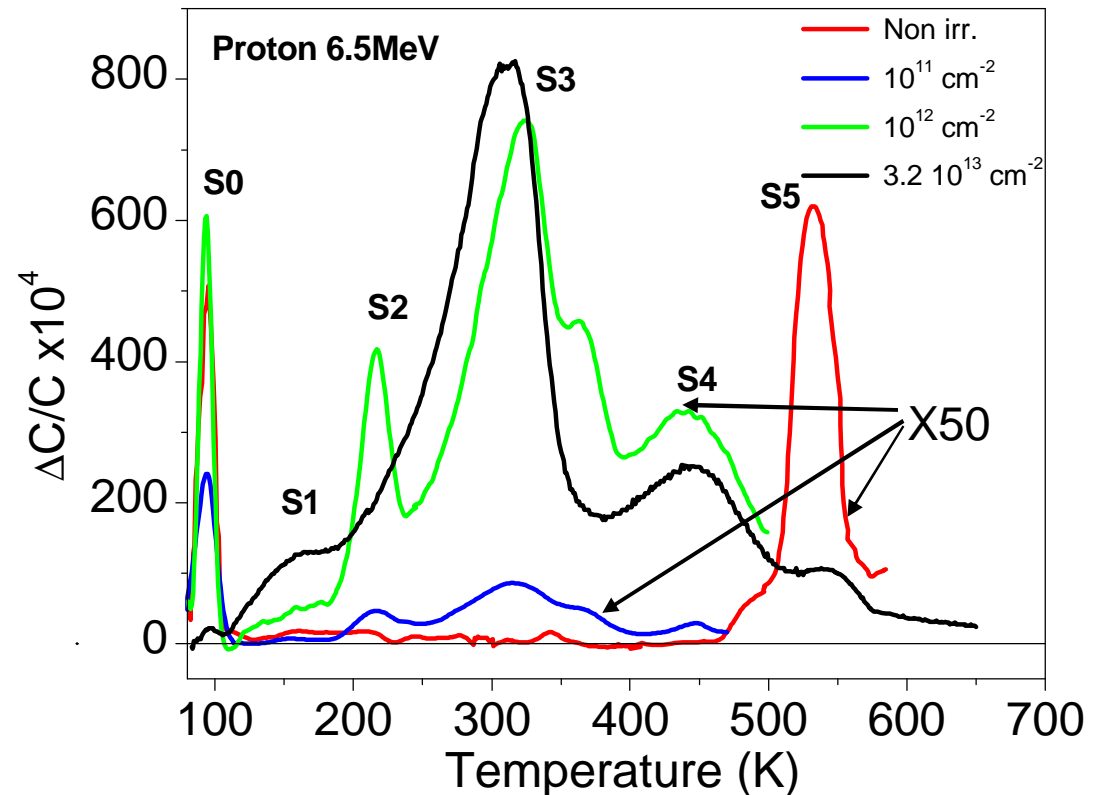
Data from F. Nava, S. Sciortino, M. Bruzzi et al., IEEE Trans. Nucl. Sci, (2004)

Proton-irradiation induced defects in epitaxial 4H-SiC Schottky Barriers

- ◆ n epilayer 7mm
- ◆ $N_{\text{eff}} \sim 7 \cdot 10^{15} \text{cm}^{-3}$
- ◆ Schottky Barriers Ti or Ni
- ◆ Ohmic contacts Ti/Ni/Ag
- ◆ Deep levels by C-DLTS
- ◆ 6.5MeV p up to $6.4 \times 10^{13} \text{cm}^{-2}$

Six traps detected after irradiation. High generation coefficients.

- ◆ $E = 0.18 - 1.22 \text{eV}$
- ◆ $S = 10^{-13} - 10^{-18} \text{cm}^{-2}$
- ◆ $N_t = 10^{11} - 5 \times 10^{14} \text{cm}^{-3}$



Data from A. Castaldini, A. Cavallini et al.

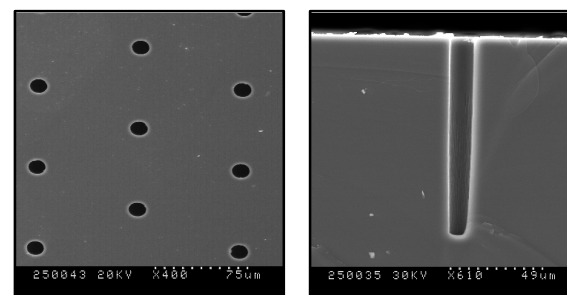
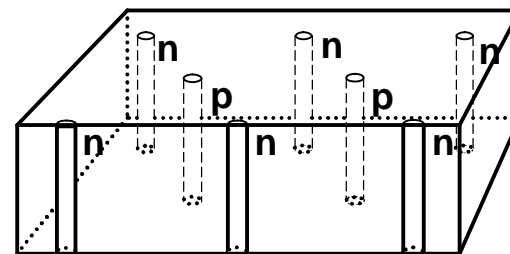
Devices irradiated up 10^{16}cm^{-2} 24GeV protons (CERN) and fast neutrons (Ljubljana). Measurements are in progress.

Device Engineering: 3D detectors

proposed by Sherwood Parker

- Electrodes:
 - narrow columns along detector thickness-“3D”
 - diameter: $10\mu\text{m}$ distance: $50 - 100\mu\text{m}$
- Lateral depletion:
 - lower depletion voltage needed
 - thicker detectors possible
 - fast signal
- Hole processing :
 - Dry etching, Laser drilling, Photo Electro Chemical
 - Present aspect ratio (RD50) 13:1, Target: 30:1
- Electrode material
 - Doped Polysilicon

Present size
up to $\sim 1\text{cm}^2$



see S. Parker talk, June 17

Advantage: application possible with all radiation-hard materials.

Within RD50, IRST-Trento is developing 3D detectors, in collaboration with CNM Barcelona. See M. Boscardin talk, June 17

Summary

- Possible radiation hard materials for tracker detectors at SuperLHC have been selected by CERN R&Ds as: **Defect engineered Si, diamond (poly- and single-crystal) and epitaxial SiC.**
- **Si (RD50):** At the fluence of 10^{16}cm^{-2} (Innermost layer of a SLHC detector) the active thickness of any material is significantly reduced due to trapping. Promising results of CCE on microstrip n-in-p detectors produced with oxygenated Si irradiated up to 7×10^{15} [$24\text{GeVp}/\text{cm}^2$] **have been measured within RD50: 6500e corresponding to 90mm ccd.** The effect of oxygen in CCE on CZ Si is still under study.
- **SiC (RD50):** 100% CCE over 40mm epilayer (2200e). Thicker epilayers needed (up to 100mm). Radiation hardness under study.
- **Diamond polycrystalline (RD42)*:** achieved 270mm ccd (mp signal: 8000e), deteriorates to 80% after $2 \times 10^{15}\text{cm}^{-2}$ 24GeV p, need to extend measurements to 10^{16}cm^{-2} .
- **Diamond single crystal (RD42)*:** achieved 550mm CCE. Limited size of 6mm diameter, no radiation hardness study available in literature.

***Data from RD42, NIMA Sept. 2003, more on H.Kagan talk**